

<https://www.spst-photopolymer.org>

Call for Papers
(Ver. 2021.03.05)

ICPST-38

The 38th International Conference
of
Photopolymer Science
and
Technology
Materials & Processes
for
Advanced Lithography,
Nanotechnology and Phototechnology

June 15 - 16, 2021

Online Meeting

**Sponsored by the Society of Photopolymer
Science and Technology (SPST)**

In Cooperation with
The Technical Association of
Photopolymers, Japan
The Chemical Society of Japan
The Society of Polymer Science, Japan
Endorsed by
The Japan Society of Applied Physics

Introduction

The 38th International Conference of Photopolymer Science and Technology, Materials & Processes for Advanced Lithography, Nanotechnology and Phototechnology (**ICPST-38**) organized by SPST will be held by **ONLINE MEETING** on **June 15 - 16, 2021**. All the contributors of papers on the scientific progress and the technical development of photopolymers are cordially invited.

1) Live online conference by ZOOM, June 15 and 16, 2021

June 15	June 16
Opening Session (21:00 - 21:10 JST)	Panel Symposium II (21:30 - 23:30 JST)
Plenary Talk (21:10 – 21:55 JST)	“Biomimetics : Learn from Nature”
Panel Symposium I (21:55 – 23:30 JST) “ EUV Lithography toward 10 nm and below – Prospect of Achievement for Both Highly Sensitive and low LWR EUV Resist “	

2) On demand streaming by Vimeo

Plenary, Keynote lecture, Invited talk, Regular talk

Period: June 15 – July 14, 2021 (Total one month)

Scopes

The conference covers a wide range of topics relevant to photopolymer science and technology in the following fields:

A. English Symposia

- A1. Next Generation Lithography, EB Lithography and Nanotechnology
- A2. Nanobiotechnology
- A3. Directed Self Assembly (DSA)
- A4. Computational / Analytical Approach for Lithography Processes
- A5. EUV Lithography
- A6. Nanoimprint
- A7. 193 nm Lithography Extension and EUV HVM Readiness
- A8. Photopolymers in 3-D Printing / Additive Manufacturing
- A9. 2D and Stimuli Responsive Materials for Electronics & Photonics
- A10. Strategies and Materials for Advanced Packaging, Next Generation MEMS, Flexible Devices
- A11. Chemistry for Advanced Photopolymer Science
- A12. Organic and Hybrid Materials for Photovoltaic and Optoelectronic Devices
- A13. Fundamentals and Applications of Biomimetics Materials and Processes
- A14. General Scopes of Photopolymer Science and Technology
- P1. Panel Symposium “EUV Lithography toward 10 nm and below – Prospect of Achievement for Both Highly Sensitive and low LWR EUV Resist “
- P2. Panel Symposium "Biomimetics: Learn from Nature"

B. Japanese Symposia

- B1. Polyimides and High Temperature Polymers
-Functionalization and Practical Applications-
- B2. General Scopes of Photopolymer Science and Technology

Language & Presentation

English is used for presentations in English Symposia and Panel Symposium.

Japanese and English are used for presentations in Japanese Symposia. Each presentation will not be

longer than 20 minutes including discussion except for the notified lectures.

Application to Scientific Program

Apply to [Conference → Presentation-Info Submission] at the SPST Homepage (www.spst-photopolymer.org/) before **February 14, 2021**.

Editorial Office:

Assoc. Prof. Hiroyuki Mayama
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Papers

Papers submitted to ICPST-38 are published in Journal of Photopolymer Science and Technology, Vol. 34 (2021) after reviewing on the Journal's standard. Journal will be distributed to each participant during the conference. Preparation of manuscripts for the Journal should be followed to "Instructions to Authors" and "Manual for Manuscript Writing". Submit the manuscripts to [Journal → Submission & Reviewing of MS] at the SPST Homepage before April 1, 2021. The Journal will be published and mailed before ICPST-38.

Registration for Participants

All the participants including speakers are requested to register in [Conference → Registration] at the SPST Homepage.

Early-bird Registration Period: Feb. 1 (Mon), 2021 (17:00, JST) ~ May 25 (Tue), 2021 (23:59, JST) *The manuscript will be delivered by post before starting the conference.

Registration Period: May 26 (Wed), 2021 (00:00, JST) to Jun. 16 (Wed), 2021 (23:59, JST)

Registration Method

All the participants including speakers are requested to register from the Registration of ICPST-38 Homepage.

For those who have completed the registration and payment by May 25 (Tue), we will be delivered the manuscript by post before starting the conference.

- Cancellation will not be accepted after payment of registration fee.
- No invoice will be issued.

Conference Office

The 38th International Conference of Photopolymer Science and Technology (ICPST-38)
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Local Committee, Chairperson: Takashi Karatsu

<https://www.spst-photopolymer.org>

講演募集

(2021.03.05改訂版)

ICPST-38

第38回

国際フォトポリマーコンファレンス

リソグラフィ、ナノテクノロジー、

フォトテクノロジー

-材料とプロセスの最前線-

2021年6月15日（火）～16日（水）

オンライン開催

主催 フォトポリマー学会（SPST）

協賛 フォトポリマー懇話会、

日本化学会、高分子学会

後援 応用物理学会

第38回国際フォトポリマーコンファレンスを下記の要領で開催いたします。
フォトポリマーに関心をお持ちの方々は是非、御参加下さい。

日 時 2021年6月15日(火)～16日(水)

開催方法 オンライン開催

1) Live online conference by ZOOM, June 15 and 16, 2021

June 15	June 16
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2) On demand streaming by Vimeo

Plenary, Keynote lecture, Invited talk, Regular talk

Period: June 15 – July 14, 2021 (Total one month)

講演内容

フォトポリマーに関する科学と技術の研究報告

A. 英語シンポジウム

- A1. Next Generation Lithography, EB Lithography and Nanotechnology
- A2. Nanobiotechnology
- A3. Directed Self Assembly (DSA)
- A4. Computational / Analytical Approach for Lithography Processes
- A5. EUV Lithography
- A6. Nanoimprint
- A7. 193 nm Lithography Extension and EUV HVM Readiness
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- A9. 2D and Stimuli Responsive Materials for Electronics & Photonics
- A10. Strategies and Materials for Advanced Packaging, Next Generation MEMS, Flexible Devices
- A11. Chemistry for Advanced Photopolymer Science
- A12. Organic and Hybrid Solar Cells – Materials, Device Physics, and Processes
- A13. Fundamentals and Applications of Biomimetics Materials and Processes
- P1. “EUV Lithography toward 10 nm and below – Prospect of Achievement for Both Highly Sensitive and low LWR EUV Resist “
- P2. "Biomimetics: Learn from Nature"

B. 日本語シンポジウム

- B1. ポリイミド及び高温耐熱樹脂-機能化と応用
- B2. 一般講演: (1) 光物質科学の基礎 (光物理過程、光化学反応など)、(2) 光機能素子材料 (分子メモリー、情報記録材料、液晶 など)、(3) 光・レーザー・電子線を活用する合成・重合・パターンニング、(4) フォトファブリケーション (光成形プロセス、リソグラフィ)、(5) レジスト除去、エッチング、洗浄、(6) 装置 (光源、照射装置、計測、プロセスなど)

講演時間と言語

原則として討論時間を含め20分。英語シンポジウムは英語、日本語シンポジウムは日本語及び英語

講演申込

学会 HP(www.spst-photopolymer.org/)

[日本語ページ → 日本語講演発表申込] から申し込んでください。

申込締切

2021年2月14日(日)

論文の出版

ICPST-38 の論文は Journal of Photopolymer Science and Technology Vol. 34 (2021)に Journal 基準による審査を経て出版されます。論文原稿は、Journal 投稿規定に従って完全原稿を作成し、2021年4月1日(木)までに学会 HP (<http://www.spst-photopolymer.org/>)の [Journal → Submission& Reviewing of MS] に投稿してください。

JPST Vol. 34 は ICPST-38 開催前に郵送いたします。

出版局事務局

〒078-8510 北海道旭川市緑が丘東2条1丁目1-1

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参加登録予約締切

早期登録期間：2021年2月1日(月) 17:00 (JST) ~ 5月25日(火) 23:59 (JST)

参加登録期間：2021年5月26日(水) 00:00 (JST) ~ 6月16日(水) 23:59 (JST)

参加登録方法:

講演者を含む全参加者はフォトポリマー学会の学会 HP (www.spst-photopolymer.org/) [日本語ページ → 参加登録]より登録をお願い致します。参加費支払はクレジットカード払いのみとなっております。5月25日(火)までに参加登録と決済まで完了された方には、会期前までに論文集を郵送いたします。

- ・お支払い完了後のキャンセルは一切受け付けておりません。
- ・請求書は発行しておりません。
- ・郵便振込ではお支払いいただけませんのでご注意ください。

参加登録費

区 分

一般

¥35,000円

学生

¥10,000円

第38回 国際フォトポリマーコンファレンス事務局

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フォトポリマー学会 (SPST)

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